

	<b>Hits</b>	<b>Search Text</b>	<b>DBs</b>
<b>44</b>	101	((resist or photoresist)) and (resin\$4 same (water\$5soluble) same (thicken\$5 or enhanc\$4 or smooth\$6 or shrinking or coat\$4) same (cationic or ester or (quaternary near5 amide))) and (surfactant same (cationic or anionic or amphoteric))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
<b>45</b>	45	((resist or photoresist)) and (resin\$4 same (water\$5soluble) same (thicken\$5 or enhanc\$4 or smooth\$6 or shrinking or coat\$4) same (cationic or ester or (quaternary near5 amide)) same (surfactant)) and (surfactant same (cationic or anionic or amphoteric))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB